Supplementary Information for:

Thermoelectric properties of the aliovalent half-Heusler alloy $Zn_{0.5}Ti_{0.5}NiSb$ with intrinsic low thermal conductivity

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Table S1: Half-Heusler compositions for hot-pressed $Zn_{1-x}Ti_xNiSb$ disks derived from EDXelemental maps shown in Fig. S1.

Nominal Composition	EDX Composition
$Zn_{0.35}Ti_{0.65}NiSb$	$Zn_{0.32}Ti_{0.65}NiSb_{1.02}$
$Zn_{0.40}Ti_{0.60}NiSb$	Zn _{0.39} Ti _{0.61} NiSb
$Zn_{0.45}Ti_{0.55}NiSb$	$Zn_{0.42}Ti_{0.54}NiSb_{1.03}$
$Zn_{0.50}Ti_{0.50}NiSb$	$Zn_{0.47}Ti_{0.53}NiSb$
$Zn_{0.55}Ti_{0.45}NiSb$	$Zn_{0.55}Ti_{0.46}NiSb_{1.02}$
$Zn_{0.60}Ti_{0.40}NiSb$	$Zn_{0.58}Ti_{0.41}NiSb_{1.01}$

	E _g (eV)	ρ ₀ (μ Ω. m)	B(×10 ⁻⁴ μΩ.m.K ^{-1.5)}	Α (μΩ.m)	ρ ₀ /B (K ^{1.5})
n-type					
Zn _{0.35} Ti _{0.65} NiSb	0.39 (fixed)	7(1)	2.5(3)	5.4(1)	27500
Zn _{0.40} Ti _{0.60} NiSb	0.39 (fixed)	14(1)	4.7(3)	4.0(1)	29978
Zn _{0.45} Ti _{0.55} NiSb	0.39(2)	33(3)	-	2.0(1)	-
p-type					
$Zn_{0.50}Ti_{0.50}NiSb$	0.39(2)	53(3)	-	2.1(1)	-
Zn _{0.55} Ti _{0.45} NiSb	0.39 (fixed)	15(1)	-	1.8(1)	-
Zn _{0.60} Ti _{0.40} NiSb	0.39 (fixed)	7(1)	0.7(1)	1.9(1)	105980

Table S2: Overview of resistivity fit parameters for the $Zn_{1-x}Ti_xNiSb$ samples,¹ see manuscript for further details.

Table S3: Measured, crystallographic and % density of the hot pressed $Zn_{1-x}Ti_xNiSb$

 $(0.4 \le x \le 0.65)$ disks characterised in this manuscript.

Composition	Measured Density (g.cm ⁻³)	Crystallographic Density (g.cm ⁻³)	% Density
$Zn_{0.35}Ti_{0.65}NiSb$	7.37(2)	7.58	97.2
$Zn_{0.40}Ti_{0.60}NiSb$	7.41(2)	7.58	97.7
Zn _{0.45} Ti _{0.55} NiSb	7.48(2)	7.59	98.5
$Zn_{0.50}Ti_{0.50}NiSb$	7.5(2)	7.60	98.7
$Zn_{0.55}Ti_{0.45}NiSb$	7.51(2)	7.60	98.8
$Zn_{0.60}Ti_{0.40}NiSb$	7.56(2)	7.61	99.3



Figure S1: Backscattered Secondary Electron SEM images, at% composite and individual elemental at% maps for n-type $Zn_{1-x}Ti_xNiSb$ disks.



Figure S2: Backscattered Secondary Electron SEM images, at% composite and individual elemental at% maps for p-type $Zn_{1-x}Ti_xNiSb$ disks.



Figure S3: Temperature dependence of $\ln[p(T)]$ plotted against T⁻¹ and T^{-0.25} to check for pure thermally activated semiconducting and variable range hopping transport in **(a-b)** n-type and **(c-d)** p-type Zn_{1-x}Ti_xNiSb.



Figure S4: Temperature dependence of the weighted mobility (μ_w) calculated from S(T) and $\rho(T)$ for (a) n-type and (b) p-type Zn_{1-x}Ti_xNiSb.²



Figure S5: Temperature dependence of the (a) thermal diffusivity, (b) calculated Lorenz number,³ and (c) electronic thermal conductivity ($\kappa_{el} = LT/\rho$) for the Zn_{1-x}Ti_xNiSb samples.



Figure S6: Thermal cycling for the best performing n-type $Zn_{0.4}Ti_{0.6}NiSb$ (**a-c**) and p-type $Zn_{0.6}Ti_{0.4}NiSb$ (**d-f**) samples. The first measurement on heating is slightly offset, but subsequent cooling-heating measurements fall on top of each other.

References

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